

ABSTRACT

A pattern region of a working reticle is divided into existing pattern portions and newly-forming pattern portions. With respect to the existing pattern portions, already-formed master reticle patterns are reduction-projected while stitching screens using an optical-type projection exposure apparatus. With respect to the newly-forming portions, enlarged patterns are formed by an electron beam drawing apparatus to form new master reticles, and reduced images of the newly formed master reticles are exposed while stitching screens using an optical-type projection exposure apparatus.